

Formation of 4-biphenyl radicals (*cf.*, Ref. 4) is supported by formation of considerable amounts of 4-iodobiphenyl by photolysis of a solution of 4-bromobiphenyl in benzene, to which iodine was added to trap the radicals.

While we have observed earlier that biphenyl formation in the case of 4-iodobiphenyl photolysis in benzene can be markedly increased by rigorous removal of oxygen from the system,³ no such procedures are required to observe the high yields of biphenyl in the case of 4-bromobiphenyl. Indeed, the biphenyl/*p*-terphenyl ratio approaches the theoretical limit of unity—showing that hydrogen transfer to the 4-biphenyl radical, from intermediates (A) or (B), or possibly from hydrogen bromide, is efficient in the case of the bromine analogue. Equations 3, 5, and 9 represent the possible hydrogen transfer steps, although step 9 is not significant, as shown by the finding of only 1% bromobenzene. As expected, addition

of hydrogen bromide to a solution of 4-iodobiphenyl or 4-bromobiphenyl in benzene, raises biphenyl formation on photolysis through step 5. The fate of bromine in the above reactions has yet to be ascertained.

The 4-halogenobiphenyls are thus increasingly resistant to photolysis in the order of the bond strengths of the corresponding substances. While this limits their utility for synthetic purposes, the information here recorded should have general value for predicting results of photolysis of selected mixed dihalogeno-aromatic compounds, which may have synthetic and mechanistic interest. The differences in product distributions in the case of the 4-bromobiphenyl photolysis in benzene, compared to 4-iodobiphenyl, can be rationalized on a free-radical mechanism and on the relative reactivities of bromine atoms *versus* iodine atoms, in the benzene solutions.

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¹ W. Wolf and N. Kharasch, *J. Org. Chem.*, 1965, **30**, 2493.

² N. Kharasch, W. Wolf, T. Erpelding, P. G. Naylor, and L. Tokes, *Chem. and Ind.*, 1962, 1760.

³ N. Kharasch and R. K. Sharma, *Chem. Comm.*, 1966, 106.

⁴ J. Szychliński and L. Litwin, *Roczniki Chem.*, 1963, **37**, 671.

⁵ N. Kharasch and P. G. Naylor, unpublished work; *cf.* also Ref. 2.